

L Number	Hits	Search Text	DB	Time stamp
1	9	upper adj buried adj oxide	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/04 16:59
2	97	top adj buried adj oxide	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/04 20:26
3	59	first adj buried adj oxide	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/04 17:07
4	46	second adj buried adj oxide	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/04 17:09
5	25	(plurality or multiple or multiplicity) adj buried adj oxide	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/04 17:54
6	0	(stress adj relief adj (film or layer or region)) adj buried adj oxide	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/04 17:55
7	0	(germanium adj (film or layer or region)) adj buried adj oxide	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/04 17:56
8	0	(stress adj relief adj (film or layer or region)) with (buried adj oxide)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/04 17:56
9	10	(germanium adj (film or layer or region)) with (buried adj oxide)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/04 18:23
10	651	thermal adj expansion adj coefficient adj silicon	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/04 18:41
11	2	thermal adj expansion adj coefficient adj silicon adj greater	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/04 18:42
12	0	thermal adj expansion adj coefficient adj oxide adj greater	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/04 18:42
13	0	thermal adj expansion adj coefficient adj oxide adj less	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/04 18:43
14	61	thermal adj expansion adj coefficient adj oxide	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/04 19:19

15	1	thermal and 5071785.pn.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/04 19:20
16	1	coefficient and 5071785.pn.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/04 19:35
17	4	buried adj composite adj (layer or film)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/04 19:36
18	0	composite adj (layer or film) adj silicon adj germanium	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/04 19:37
19	8	(composite adj (layer or film)) with (silicon adj germanium)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/04 19:37
20	2343	(buried adj oxide) and 257/\$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/04 20:28